

# **APPENDIX C**

**(CLEAN VERSION OF ALL PENDING CLAIMS)**

**(Serial No. 09/854,759)**

## CLAIMS

What is claimed is:

1. (Amended) A method of attaching a wafer having bumps on a surface thereof, comprising:  
attaching a tape having an adhesive and a backing on at least a portion of said surface of said wafer;  
providing a wafer mount having a suction surface; and  
applying a suction force to said backing of said tape.

2. The method of claim 1, further comprising:  
removing wafer material from a back surface of said wafer.

3. The method of claim 1, wherein said attaching a tape having an adhesive and a backing includes:  
conforming said backing to include a substantially planar surface on at least a portion thereof.

4. (Amended) The method of claim 3, wherein said applying said suction force to said backing of said tape comprises applying a suction force to said substantially planar surface of said backing.

5. (Amended) The method of claim 1, wherein said attaching a tape having an adhesive and a backing comprises:  
conforming at least a portion of said adhesive of said tape to said bumps to form a substantially planar surface on said backing of said tape.

6. The method of claim 1, wherein said applying a suction force to said backing of said tape includes abutting said backing to said suction surface of said wafer mount.

7. The method of claim 1, wherein said wafer comprises a wafer having a thickness of at least about 12 mils.

Sub 7  
8. (Amended) The method of claim 2, wherein said removing comprises thinning said wafer to a thickness in the range of between about 6 mils and about 12 mils.

9. The method of claim 2, wherein said removing comprises thinning said wafer to one of about 6 mils thickness and less than about 6 mils thickness.

10. The method of claim 2, wherein said removing comprises grinding said back surface of said wafer.

11. The method of claim 2, wherein said removing comprises thinning said wafer by chemical-mechanical polishing said back surface of said wafer.

12. A method of holding a wafer having bumps on at least a portion of a surface thereof, comprising:  
applying an adhesive to a portion of said surface of said wafer;  
attaching a backing to at least a portion of said adhesive;  
providing a wafer mount having a suction surface; and  
holding said backing to said suction surface of said wafer mount using a suction force.

13. The method of claim 12, further comprising:  
removing wafer material from another surface of said wafer.

Sub 14  
14. (Amended) The method of claim 12, wherein said attaching said backing comprises:  
conforming said backing to at least a portion of said surface of said wafer to form a substantially planar surface on said backing.

15. (Amended) The method of claim 14, wherein said holding said backing to said suction surface of said wafer mount comprises applying said suction force to said substantially planar surface of said backing.

16. (Amended) The method of claim 12, wherein said attaching said backing includes conforming said adhesive and said backing to said bumps to form a substantially planar surface on said backing.

17. The method of claim 12, wherein said holding said backing to said suction surface of said wafer mount comprises abutting at least a portion of said backing to said suction surface of said wafer mount.

18. The method of claim 12, wherein said wafer comprises a wafer having a thickness of at least about 12 mils.

19. (Amended) The method of claim 13, wherein said removing comprises thinning said wafer to a thickness in the range of about 6 mils to about 12 mils.

20. The method of claim 13, wherein said removing comprises thinning said wafer to one of a thickness of about 6 mils and a thickness of about less than 6 mils.

21. (Amended) The method of claim 13, wherein said removing comprises grinding said another surface of said wafer.

22. (Amended) The method of claim 13, wherein said removing comprises thinning said wafer by chemical-mechanical polishing said another surface of said wafer.

Ab  
Sub  
Ba

23. (Amended) A method of thinning a wafer comprising:  
providing a wafer having bumps on at least a portion of a surface thereof;  
attaching an adhesive having a backing to said at least a portion of said surface of said wafer;  
providing a wafer mount having a suction surface;  
attaching said backing of said adhesive to at least a portion of said suction surface of said wafer  
mount using a suction force; and  
removing wafer material from another surface of said wafer.

---

24. The method of claim 23, wherein said attaching said adhesive having said backing  
comprises conforming said backing to include a substantially planar surface.

---

25. The method of claim 24, wherein said attaching said backing to at least a portion  
of said suction surface of said wafer mount comprises applying said suction force to said  
substantially planar surface of said backing.

---

A7  
Sub  
C17

26. (Amended) The method of claim 23, wherein said attaching said adhesive having  
said backing comprises providing an adhesive portion conforming to said bumps to form a  
substantially planar surface on said backing.

---

27. (Amended) The method of claim 23, wherein said attaching said backing to at  
least a portion of said suction surface of said wafer mount comprises abutting at least a portion of  
said backing to said at least a portion of said suction surface and wherein said suction force  
attaches said wafer to said wafer mount.

---

28. The method of claim 23, wherein said wafer comprises a wafer having a thickness  
of at least about 12 mils.

---

Sub  
C17  
A8

29. (Amended) The method of claim 24, wherein said removing comprises thinning  
said wafer to a thickness in the range of between about 6 mils and about 12 mils.

---

30. The method of claim 23, wherein said removing comprises thinning said wafer to one of about 6 mils and less than about 6 mils.

---

AA  
Sub 17  
31. (Amended) The method of claim 23, wherein said removing comprises grinding said another surface of said wafer.

32. (Amended) The method of claim 23, wherein said removing comprises thinning said wafer by chemical-mechanical polishing said another surface of said wafer.

Sub B4  
33. (Amended) A method of fabricating a wafer having a front surface having bumps thereon and a back surface, comprising:  
applying an adhesive having a backing on said bumps of said front surface of said wafer;  
providing a wafer mount having a suction surface;  
attaching at least a portion of said backing to at least a portion of said suction surface of said wafer mount using a suction force; and  
removing wafer material from said back surface of said wafer.

---

34. The method of claim 33, wherein said applying said adhesive having said backing comprises conforming said backing to include a substantially planar surface.

---

AD  
Sub 17  
35. (Amended) The method of claim 34, wherein said attaching at least a portion of said backing to at least a portion of said suction surface of said wafer mount comprises applying said suction force to at least a portion of said substantially planar surface of said backing.

36. (Amended) The method of claim 33, wherein said applying said adhesive having said backing comprises providing an adhesive portion conforming to said bumps to form a substantially planar surface on said backing.

*Q.10*  
*Sub C17*  
37. (Amended) The method of claim 33, wherein said attaching at least a portion of said backing to at least a portion of said suction surface of said wafer mount comprises abutting at least a portion of said backing to said suction surface and wherein said suction force to attach said wafer to said wafer mount.

---

38. The method of claim 33, wherein said wafer comprises a wafer having a thickness of at least about 12 mils.

39. The method of claim 33, wherein said removing comprises thinning said wafer to a thickness in the range of between about 6 mils and about 12 mils.

40. The method of claim 33, wherein said removing comprises thinning said wafer to a thickness of one of about 6 mils and less than about 6 mils.

---

*Q.11*  
*Sub C17*  
41. (Amended) The method of claim 33, wherein said removing comprises grinding said back surface of said wafer.

42. (Amended) The method of claim 33, wherein said removing comprises thinning said wafer by chemical-mechanical polishing said back surface of said wafer.

---

43. The method of claim 33, further comprising:  
removing said adhesive from said wafer.

44. The method of claim 43, further comprising:  
singulating said wafer into at least one die.

Q12  
Sub B5  
45. (Amended) A method of mounting a bumped wafer having bumps on at least a portion of a surface thereof to a wafer mounting chuck, comprising:  
applying an adhesive having a backing to at least a portion of said bumps and at least a portion of said surface of said wafer; and  
mounting said wafer to said wafer mounting chuck using a suction force communicated through said wafer mounting chuck.

46. (Amended) The method of claim 45, wherein said applying said adhesive having said backing comprises conforming said backing to include a substantially planar surface.

Sub C1  
47. (Amended) The method of claim 46, wherein said mounting said wafer to said wafer mounting chuck comprises applying said suction force to at least a portion of said substantially planar surface.

48. (Amended) The method of claim 45, wherein said applying said adhesive having said backing comprises conforming said adhesive to at least a portion of said bumps to form a substantially planar surface on said backing.

49. (Amended) The method of claim 45, wherein said mounting said wafer to said wafer mounting chuck comprises abutting at least a portion of said backing to a suction surface of said wafer mounting chuck.

50. (Amended) The method of claim 45, wherein said wafer comprises a wafer having a thickness of at least about 12 mils.

51. (Amended) A method of using a vacuum to hold a bumped wafer having a front surface having bumps thereon and a back surface, comprising:  
applying an adhesive having a backing to at least a portion of said front surface of said wafer covering at least one bump of said bumps thereon; and



holding at least a portion of said front surface of said wafer using a vacuum applied through at least a portion of a surface of a wafer mount.

52. (Amended) The method of claim 51, wherein said applying said adhesive having said backing includes conforming a portion of said backing to include a substantially planar surface.

53. The method of claim 52, wherein said holding comprises applying said vacuum to said substantially planar surface of said backing.

54. (Amended) The method of claim 51, wherein said applying said adhesive having said backing over said at least one bump comprises providing an adhesive conforming to said at least one bump to form a substantially planar surface on said backing.

55. (Amended) The method of claim 51, wherein said holding comprises abutting at least a portion of said backing to said surface of the wafer mount and wherein said vacuum holds said wafer to said wafer mount.

56. The method of claim 51, wherein said wafer comprises a wafer having a thickness of at least about 12 mils.

57. (Amended) A wafer mount assembly for a wafer having a front surface having at least one bump thereon and a back surface, comprising:  
an adhesive tape having an adhesive and a backing, said adhesive tape for adhesively attaching a portion of said front surface of said wafer having said at least one bump thereon to a portion of said wafer mount assembly.

58. (Amended) The assembly of claim 57, further comprising:

a wafer mount having a vacuum surface thereon, said vacuum surface of said wafer mount for abutting at least a portion of said backing of said adhesive tape, said vacuum surface including apertures therein for communicating a vacuum therethrough.

59. (Amended) The assembly of claim 57, wherein said backing of said adhesive tape

includes a substantially planar surface for overlying said at least one bump.

60. (Amended) The assembly of claim 59, wherein said substantially planar surface of

said backing of said adhesive tape provides an area for the application of a vacuum to at least a portion of said front surface of said wafer.

61. The assembly of claim 57, wherein said backing includes a substantially planar surface overlying said at least one bump.

62. (Amended) The assembly of claim 57, wherein said adhesive attaches to said at least one bump.

63. (Amended) The assembly of claim 57, wherein said adhesive conforms to said at least one bump to form a substantially planar surface on at least a portion of said backing.

64. (Amended) The assembly of claim 57, wherein said adhesive tape substantially overlies another bump.

65. (Amended) The assembly of claim 57, wherein said wafer comprises a wafer having a thickness of at least 12 mils.

66. The assembly of claim 57, wherein said at least one bump comprises a conductive bump for electrical connection.

67. (Amended) An assembly of a bumped wafer mounted to a wafer mount for grinding, the assembly comprising:  
a wafer having a front surface and a back surface thereof, said front surface having at least one bump thereon; and  
a tape having an adhesive and a backing, said tape for adhesively attaching a portion of said wafer having said at least one bump thereon.

68. The assembly of claim 67, wherein said backing includes a substantially planar surface overlying said at least one bump.

69. (Amended) The assembly of claim 67, wherein said adhesive attaches to said at least one bump for forming a substantially planar surface on said backing.

70. (Amended) The assembly of claim 67, wherein said adhesive conforms to said at least one bump to form a substantially planar surface on a portion of said backing.

71. (Amended) The assembly of claim 67, wherein said tape substantially covers said front surface of said wafer.

72. The assembly of claim 67, wherein said at least one bump comprises a conductive bump for electrical connection.

73. The assembly of claim 67, wherein said backing comprises a resilient material.

74. (Amended) The assembly of claim 67, wherein said wafer comprises a thickness of at least 12 mils prior to being mounted to said wafer mount.

75. The assembly of claim 67, wherein said wafer comprises another thickness of one of about less than 6 mils and greater than about 6 mils and less than about 12 mils after grinding said back surface of said wafer.